

Custom Ptfе Corrosion Resistant 6 Inch Dual Handle Photomask Cleaning Flower Basket Rack

Item Number: PL-CP05



Introduction

High-performance custom PTFE 6-inch dual handle photomask cleaning racks offer unmatched chemical resistance for semiconductor and laboratory wet processes. These durable flower baskets ensure secure sample handling, rapid drainage, and contamination-free cleaning in aggressive acids and solvents.

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Application	Description	Key Benefit
Semiconductor RCA Cleaning	Sequential immersion of silicon wafers in SC-1 and SC-2 solutions to remove organic and metallic contaminants.	Total resistance to oxidizing agents and high-temperature acids ensures no carrier degradation.
Photomask Etching	Holding 6-inch photomasks during the removal of chrome or other light-blocking layers using aggressive etchants.	Secure positioning prevents mask vibration, ensuring high-fidelity pattern transfer and zero surface scratching.
Solar Cell Texturing	Process of creating micro-pyramids on silicon surfaces using KOH or HF/HNO ₃ mixtures to improve light absorption.	Durable dual-handle design allows for safe handling in high-volume, deep-tank industrial environments.
MEMS & Microfluidics	Cleaning and etching of glass or silicon substrates used in the fabrication of Micro-Electro-Mechanical Systems.	Material purity prevents the introduction of trace impurities that could interfere with micro-scale device function.
Trace Analysis Labware	Holding beakers, lids, or small components during specialized acid steam cleaning or soaking.	Guaranteed absence of metal ions (ion-free) makes it the gold standard for ultra-trace element analysis support.
Conductive Glass Prep	Cleaning of ITO or FTO coated glass substrates for OLED or perovskite solar cell research.	Grid design allows for complete fluid contact with the conductive layer while protecting the substrate edges.
Wet Chemical Developing	Transporting exposed photoresist-coated wafers through developer solutions in lithography workflows.	Chemical stability across various organic developers ensures consistent results and zero material interaction.

Parameter	Specification Details (Model: PL-CP05)
Primary Material	100% High-Purity Virgin Polytetrafluoroethylene (PTFE)
Substrate Compatibility	Standard 6-inch (152.4 mm) Photomasks, Wafers, or Glass
Handle Configuration	Dual-Handle Reinforced Support for balanced vertical lifting
Temperature Resistance	-200°C to +260°C (-328°F to +500°F)
Chemical Compatibility	Universal (All acids, bases, organic solvents, and piranha solutions)
Slot Configuration	Customizable slot width, pitch, and total capacity (standard 10/25 slots)
Structural Features	CNC-machined grid base for rapid drainage; rounded sample contact points
Surface Finish	Smooth, non-porous machined PTFE surface (Low friction)
Handle Height	Customizable to suit specific cleaning tank depths

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Metal Content	Zero (Metal-free construction)	